L	Hits	Search Text	DB	Time stamp
Number				
1	3387	257/69.ccls. 257/517.ccls. 257/526.ccls.	USPAT;	2004/09/01
		257/774.ccls. 257/797.ccls.	US-PGPUB;	12:37
			EPO; JPO	
-	0	"perfect alignment" with "semiconductor	USPAT;	2004/09/01
İ		mask"	US-PGPUB;	09:39
			EPO; JPO	
-	0	"perfect alignment" same "semiconductor mask"	USPAT;	2004/09/01
			US-PGPUB;	09:39
			EPO; JPO	
-	2	"perfect alignment" and "semiconductor mask"	USPAT;	2004/09/01
			US-PGPUB;	09:40
			EPO; JPO	
-	209	"shallow isolation trenches"	USPAT;	2004/09/01
			US-PGPUB;	09:40
i			EPO; JPO	
l –	59	"deep isolation trenches"	USPAT;	2004/09/01
		•	US-PGPUB;	09:40
			EPO; JPO	
_	9	"shallow isolation trenches" and "deep	USPAT;	2004/09/01
		isolation trenches"	US-PGPUB;	09:40
			EPO; JPO	
_	6	("shallow isolation trenches" and "deep	USPAT;	2004/09/01
	_	isolation trenches") and align\$4	US-PGPUB;	12:34
		, ,, ,	EPO; JPO	